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Odyssey
 2020

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The Speaker and Language Recognition Workshop
 01 - 05 Nov 2020, Tokyo, Japan
www.odyssey2020.org

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Topics

- Speaker and language recognition, verification, and identification
- Speaker and language characterization
- Features for speaker and language recognition
- Speaker and language clustering
- Multispeaker segmentation, detection, and diarization
- Language, dialect, and accent recognition
- Robustness in channels and environment
- System calibration and fusion
- Speaker recognition with speech recognition
- Multimodal speaker recognition
- Speaker recognition in multimedia content
- Machine learning for speaker and language recognition
- Confidence estimation for speaker and language recognition
- Corpora and tools for system development and evaluation
- Low-resource (lightly supervised) speaker and language recognition
- Speaker synthesis and transformation
- Human and human-assisted recognition of speaker and language
- Spoofing/presentation attacks: analysis and countermeasures
- Forensic and investigative speaker recognition
- Systems and applications

Important dates

Nov 20	Paper submission opens
Jan 27	Paper submission deadline
Mar 25	Acceptance notifications
May 18	Preliminary program
Nov 01	Tutorial day
Nov 02-05	Odyssey workshop



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